

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Huilong Zhu, et al.

Examiner: Chuong A. Luu

Serial No: 10/709,239

Art Unit: 2892

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Docket: FIS920030375US1 (17192)

For: STRUCTURES AND METHODS FOR
MANUFACTURING OF DISLOCATION
FREE STRESSED CHANNELS IN BULK
SILICON AND SOI CMOS DEVICES BY
GATE STRESS ENGINEERING WITH
SiGe AND/OR Si:C

Dated: June 20, 2008

Confirmation No: 3238

Commissioner for Patents
United States Patent Office
Alexandria, VA 23313-1450

RESPONSE UNDER 37 C.F.R. § 1.111

Sir:

In response to the Office Action dated March 20, 2008, Applicants submit the following amendments and remarks for entry of record in the above-identified patent application.

Amendments to the Claims are provided in the **Listing of Claims** beginning on page 2 of this paper.

Remarks begin on page 9 of this paper.

CERTIFICATE OF ELECTRONIC FILING

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Dated: June 20, 2008


Harry Andrew Hild Jr.